

	Hits	Search Text	DBs
27	45	((ion near9 beam) or sputter\$4) same (RF near8 (power or Watts or "W")) same (voltage or "V") same (resist or photoresist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	49	((ion near9 beam) or (sputter\$4 near16 beam) or (sputter near9 etch\$4)) same (energy near9 (voltage or "V" or watts or power)) same (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
29	269	((ion near9 beam) same ((sputter\$4 near16 beam) or (sputter near9 etch\$4)) same (irradiat\$4 or imping\$4 or bombard\$6 or expos\$4) same (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	30	((ion near9 beam) same ((sputter\$4 near16 beam) or (sputter near9 etch\$4)) same (irradiat\$4 or imping\$4 or bombard\$6 or expos\$4) same (resist or photoresist) same (harden\$6 or cur\$5 or overhang or redeposit\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB